



1755 #  
PATENT APPLICATION  
Do. No. 1941-70

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Paul J. BRUINSMA, Suresh BASKARAN, Jagannadha R. BONTA  
and Jun LIU

Serial No. 09/481,988

Examiner: P. Marcantoni

Filed: January 11, 2000

Group Art Unit: 1755

For: MESOPOROUS-SILICA FILMS, FIBERS, AND POWDERS BY EVAPORATION

Date: November 13, 2000

Box FEE AMENDMENT  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Responsive to the Office Action dated August 10, 2000, enclosed is an amendment in the above-identified application.

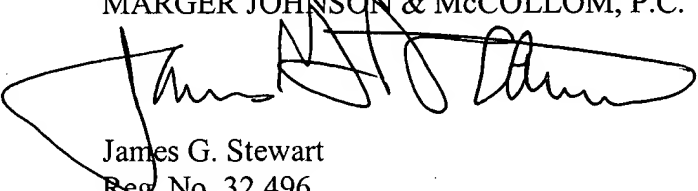
The fee has been calculated as shown below.

CLAIMS AS AMENDED					
For:	Number After Amendment	Previous Number	Extra	Rate	Additional Fee
Total Claims	75	-71	4	x \$ 9 =	\$36
Independent Claims	14	-12	2	x \$39 =	\$78
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$114

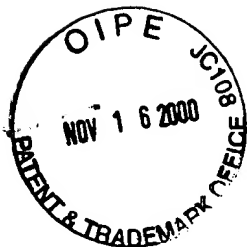
The Commissioner is hereby authorized to charge deposit account number 13-1703 the amount of \$114.

Respectfully submitted,

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James G. Stewart  
Reg. No. 32,496

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RESPONSE TO OFFICE ACTION

Responsive to the Office Action, dated August 10, 2000, please amend the application as follows.

*new matter?  
looks like it*

IN THE CLAIMS

Please amend claims 32, 53, 55, 58 and 62 as follows:

32. (Amended) A process to form mesostructured films, comprising:

(a) preparing a precursor sol containing a soluble source of a metal oxide, water, an organic solvent, surfactant and acid or base catalyst, wherein the surfactant concentration  $c_0$  [is much less than] does not exceed the critical micelle concentration and the surfactant is present as free surfactant; and

(b) depositing the precursor sol on a substrate wherein evaporation of solvent and water causes the formation of said mesostructured films on the substrate surface wherein said mesostructured films are identified by XRD peaks in the range  $2\theta$ - $2^\circ$ - $6^\circ$  hexagonal, cubic, or lamellar electron diffraction patterns.

53. (Amended) The method of claim 42 wherein the mesoporous film has a refractive index [of less than] as low as approximately 1.16.

*ok no longer new matter  
see col. 10 lines 10-11*

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